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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Masaya ISHIDA et al.

Application No.: 10/026,653

Filed: December 27, 2001

Docket No.: 111594

For: MANUFACTURING METHOD OF MOLECULAR FILM PATTERN, MOLECULAR FILM PATTERN, MANUFACTURING METHOD OF SEMICONDUCTOR DEVICE, SEMICONDUCTOR DEVICE, MANUFACTURING METHOD OF ELECTRO-OPTICAL DEVICE, ELECTRO-OPTICAL DEVICE, MANUFACTURING METHOD OF ELECTRONIC DEVICE, AND ELECTRONIC APPARATUS

PRELIMINARY AMENDMENT

Director of the U.S. Patent and Trademark Office
Washington, D. C. 20231

Sir:

Prior to initial examination, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 12-16, 18, 22 and 23 as follows:

12. (Amended) A method for manufacturing a molecular film pattern according to Claim 3,

wherein R¹ of the organic silicon compound is a perfluoroalkyl group.

13. (Amended) A method for manufacturing a molecular film pattern according to Claim 3,

wherein R¹ of the organic silicon compound is a trifluoromethyl group.

14. (Amended) A method for manufacturing a molecular film pattern according to Claim 1,

wherein the thickness of the molecular film is 3 nm or less.

15. (Amended) A molecular film pattern formed by a method for manufacturing a molecular film pattern according to Claim 1.

16. (Amended) A method for manufacturing a semiconductor device comprising:
a step of forming a molecular film pattern according to a method for manufacturing a molecular film pattern recited in Claim 1.